

IN THE UNITED STATES PATENT  
AND TRADEMARK OFFICE

Attorney Docket No. UCF-287DIV (which is a divisional of application SN: 09/881,620 filed 06/14/2001 and U. S. Provisional application 60/242,102 filed October 20, 2000)

Serial No.: 09/\_\_\_\_

Filed: \_\_\_\_ / \_\_\_\_ / \_\_\_\_

Divisional Application of Serial No.: 09/881,620

Filed: 06/14/2001

First Named Inventor: Martin Richardson

For: EUV, XUV, AND X-RAY WAVELENGTH SOURCES CREATED FROM LASER PLASMA PRODUCED FROM LIQUID METAL  
SOLUTIONS, Examiner: COURTNEY D. THOMAS

Group: 2882

INFORMATION DISCLOSURE STATEMENT

Honorable Commissioner of Patents  
and Trademarks  
P O Box 1450  
Alexandria, VA 22313-1450

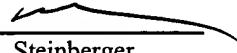
Sir:

Pursuant to 37 CFR §§ 1.97 and 1.98, record is being made below in a form PTO-1449 of documents which the Patent Office may wish to consider in connection with examination of the above-identified patent application. It is respectfully requested that the cited documents be carefully considered by the Examiner and made of record in this case. As provided in § 1.97(g), no representation is made or intended that a thorough art search was made. As provided in 37 C.F.R. § 1.97(h), this Supplemental Information Disclosure Statement does not constitute an admission of any kind, and specifically is not an admission that the documents listed on the attached PCT-1449 are, or are considered to be, material to the patentability of the above-identified patent application, as defined in 37 C.F.R. § 1.56(b).

Copies of the cited references were previously submitted to the USPTO in the parent application No.: 09/881,620 filed 06/14/2001 and made of record. Applicants claim priority to said application under 35 U. S. C. §120. Accordingly, copies of those documents are not provided with this Statement pursuant to 37 CFR § 1.98(d).

It is respectfully requested that the cited documents be carefully considered by the Examiner and made of record in the case.

Respectfully submitted,

  
Brian S. Steinberger  
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Date: 3/8/07

## IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re Application of )

**MARTIN RICHARDSON**)

Serial No: TBA )

Filed: Concurrently Herewith )

For: **EUV, XUV, AND X-RAY WAVELENGTH SOURCES CREATED FROM LASER PLASMA PRODUCED  
FROM LIQUID METAL SOLUTIONS**)INFORMATION DISCLOSURE STATEMENT

Honorable Commissioner of Patents  
and Trademarks  
Washington DC 20231

Sir:

Pursuant to the requirements of 37 CFR 1.97 and 1.98, Applicant hereby requests that the references listed in the attached form PTO-1449 be considered and made of record in the above-identified application.

Favorable consideration of the application at an early date is respectfully solicited.

Respectfully submitted,

By: 

Brian S. Steinberger  
Attorney for Applicant  
Registration No. 36,423  
101 Brevard Avenue  
Cocoa, FL 32922  
Client no.: 23717

Date: 6/14/01

**US DEPARTMENT OF COMMERCE  
PATENT AND TRADEMARK OFFICE**

**APPLICANT: MARTIN RICHARDSON  
FOR: EUV, XUV, AND X-RAY WAVELENGTH SOURCES CREATED FROM LASER PLASMA  
PRODUCED FROM LIQUID METAL SOLUTIONS**

**LIST OF ART CITED BY APPLICANT**

**U.S. PATENT DOCUMENTS**

EXAMINER	DOCUMENT NO.	DATE	NAME	CLASS	SUBCLASS	FILING DATE
AA	4,024,400	05/17/77	Blytas et al.	250	432	05/13/76
AB	4,328,464	05/04/82	Pivirotto	330	4.3	02/07/80
AC	4,700,371	10/13/87	Forsyth et al.	378	34	11/08/84
AD	4,723,262	02/02/88	Noda et al.	378	119	12/26/85
AE	4,866,517	09/12/89	Mochizuke et al.	378	119	09/10/87
AF	4,953,191	08/28/90	Smither et al.	378	143	07/24/89
AG	5,126,755	06/30/92	Sharpe et al.	346	75	03/26/91
AH	5,142,297	08/25/92	Eijkman et al.	346	1.1	03/26/90
AI	5,148,462	09/15/92	Spitsyn et al.	378	143	04/08/91
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AK	5,243,638	09/07/93	Wang et al.	378	119	03/10/92
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AM	5,459,771	10/17/95	Richardson et al.	378	119	04/01/94
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AQ	6,002,744	12/14/99	Hertz et al.	378	119	10/21/98

**FOREIGN PATENT DOCUMENTS**

FA	JA57/41167	1982	
FB	JA0267895	11/90	Iwamatsu

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PRODUCED FROM LIQUID METAL SOLUTIONS

LIST OF ART CITED BY APPLICANT

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OTHER ART (Including Author, Title, Date, Pertinent Pages, Etc.)

OA T.P. Donaldson, *SOFT X-RAY SPECTROSCOPY OF LASER-PRODUCED PLASMAS WITH A CONVEX MICA CRYSTAL SPECTROMETER*, X-Ray Astronomy Group, Vol. 9, P. 1645-1655, 1 March 1976

OB T. Mochizuki, *SOFT X-RAY OPTICS AND TECHNOLOGY*, Proceedings Of SPIE-The International Society For Optical Engineering, Vol. 733, P. 23-27, December 1986

OC Martin Richardson, *LASER PLASMA SOURCE FOR X-RAY PROJECTION LITHOGRAPHY*, Laser-Induced Damage In Optical Materials, Vol. 1848, P. 483-500, 1992

OD W.T. Silfvast, *LASER-PRODUCED PLASMAS FOR X-RAY PROJECTION LITHOGRAPHY*, American Vacuum Society, P. 3126-3133, 4 August 1992

OE F. Jin, *MASS LIMITED PLASMA CYROGENIC TARGET FOR 13NM POINT X-RAY SOURCES FOR LITHOGRAPHY*, Application of Laser Plasma Radiation, Vol. 2015, P. 1-9, August 1993